

3.
8. (Amended) A mask according to claim ²7, wherein said bright pattern is regularly arranged.

C₁ Cont.
4.
9. (Amended) A mask according to claim ²7, wherein said bright pattern is irregularly arranged.

8.
11. (Amended) A mask according to claim ⁷10, wherein the maximum value of said pitch is determined so that a concave and convex pattern formed by transferring said dark pattern on said mask onto a substrate is not more than resolution of an alignment sensor.

C₂
9.
12. (Amended) A mask according to claim ⁷10, wherein said dark pattern is regularly arranged.

10.
13. (Amended) A mask according to claim ⁷10, wherein said dark pattern is irregularly arranged.

13.
24. (Amended) An exposure apparatus comprising:
a projection optical system which projects an image of a mark on a mask onto a substrate to form an alignment mark on said substrate; and
an alignment sensor which detects said alignment mark formed on said substrate,
wherein said alignment mark includes a plurality of first patterns having a height and a second pattern for preventing a file covering the alignment mark from being depressed.